## **CLAIM AMENDMENTS:**

Please amend claims 1, 20 and 21, and cancel claims 10-19 and 27-36 as follows:

1. (Currently Amended) A three dimension (3D) polysilicon read only memory (ROM), at least comprising:

a silicon substrate;

an isolated silicon dioxide (SiO2) layer, which is deposited on the silicon substrate;

a N-Type heavily doped (N+) polysilicon layer, which is deposited on the isolated SiO<sub>2</sub> layer and is further defined defines a plurality of parallel, separate word lines (WL);

a first oxide layer, which is filled in the space between the word lines;

a dielectric layer, which is deposited on the word lines and the first oxide layer;

a P-Type lightly doped (P-) polysilicon layer, which is deposited on the dielectric layer and is further defined defines a plurality of parallel, separate bit lines (BL), wherein the bit lines overlap the word lines, from a top view, to form a shape approximately as defines a cross;

at least a neck structure, which are individually formed between the first polysilicon layer and the second polysilicon layer the N-type heavily doped (N+) polysilicon layer and the P-type lightly doped (P-) polysilicon layer by isotropically etching the dielectric layer and using dilute hydrofluoric acid (HF); and

a second oxide layer, which is filled in the space between the bit lines and is on the word lines and the first oxide layer.

**AMENDMENT** 

(10/728,767)